

## Two-Valley Transport Equation Approach for AlGaAs/GaAs HBTs

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Transport equations for particle, momentum and energy densities in two conduction bands are applied to a self-consistent numerical simulation of heterojunction bipolar transistors. Simple formulas for the relaxation frequencies are proposed, by which the variation of the conduction band energy and doping concentration in a heterostructure device are easily taken into account. The electron transport in the AlGaAs/GaAs heterojunction bipolar transistor with two different collector structures is analyzed and discussed.

### 1. Introduction

We present in this paper a novel HBT model in which the electron transport equations for particle, momentum and energy densities in two conduction bands are employed. The collision terms in the transport equations are approximated by the relaxation times which are functions of electron energy. The relaxation times are expressed by simple interpolation formulas whose parameters can be modified in conformity with the variation of the band structure and doping concentration in a heterostructure device. The devices simulated are AlGaAs/GaAs HBT's with a wide-gap emitter, a graded-gap base and two different structures for collector space-charge region (SCR).

### 2. Simulation Method

The conservation equations for particles, momentum and energy are employed in order to describe the electron motion. We employed a similar relaxation time approximation proposed by Stewart et al. [1] as follows :

$$\left(\frac{\partial n_i}{\partial t}\right)_c = -n_i f_{nij}(w_i) + n_j f_{nji}(w_j) \quad (1)$$

$$\left(\frac{\partial p_i}{\partial t}\right)_c = -p_i f_{pi}(w_i) - p_i f_{nij}(w_i) \quad (2)$$

$$\left(\frac{\partial w_1}{\partial t}\right)_c = -(w_1 - w_0) f_{w1}(w_1) + \frac{w_{12}(w_1)}{n_1} \left(\frac{\partial n_1}{\partial t}\right)_c \quad (3)$$

$$\left(\frac{\partial w_2}{\partial t}\right)_c = -(w_2 - w_0) f_{w2}(w_2) \quad (4)$$

where  $i$  is the index of the conduction bands ( $i=1$  for  $\Gamma$ -valley and  $i=2$  for L-valleys).  $n_i$  is the electron density,  $p_i$  is the mean momentum density, and  $w_i$  is the mean energy density per electron.  $f_{nij}$  and  $f_{nji}$  are the relaxation frequencies which are related to the variation of electron density due to the intervalley transfer.  $f_{pi}$  is the momentum relaxation frequency, and  $f_{w1}$  and  $f_{w2}$  are the energy relaxation frequencies.  $w_{12}$  is the average transfer energy when electrons are transferred from the  $\Gamma$ -valley to the L-valleys.  $w_0$  is the background energy density associated with the lattice temperature.

The various relaxation frequencies and

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$w_{12}$  employed in Eqs. (1)-(4) are functions of electron energy  $w_1$  or  $w_2$ . These are numerically obtained by a Monte Carlo simulation by considering a uniform electric field applied across the material under study and are expressed by simple interpolation formulas presented in Table 1.

The critical energy  $w_c$  which is employed in the interpolation formulas corresponds to the energy separation between the  $\Gamma$ - and L-valleys.  $w_c$  varies consequently with material composition.

The numerical calculation regarding the transport equations for electrons and the continuity equation for holes were made self-consistently with Poisson equation.

### 3. Results and Discussion

The two HBT structures simulated are shown in Fig.1. The collector SCR is different in the two devices corresponding to conventional HBT (HBT<sub>conv</sub>) and inverted-field HBT (HBT<sub>invt</sub>). The base is linearly graded with an Al fraction  $x=0.1$  at the emitter-base junction and  $x=0.0$  at the base-collector junction.

Fig.2(a), (b) shows the carrier density profiles in HBT<sub>conv</sub> and HBT<sub>invt</sub>. The solid curves  $n_1$  and  $n_2$  show the electron densities in the  $\Gamma$ - and L- valleys, respectively, while the dotted curves show the hole density. It is seen that the density of  $\Gamma$ -valley electrons is higher than that of the L-valley electrons in the emitter and base regions because the bottom of the L-valleys is located higher energy than the bottom of the  $\Gamma$ -valley. This changes, however, in HBT<sub>conv</sub> towards to the base-collector junction, where the high electric field causes intervalley transfer. On the contrary the L-valley electrons in HBT<sub>invt</sub> do not increase steeply near the base-collector junction but show a smooth  $\Gamma$  to L transition somewhere between the base and  $n^+$  collector. This is

$$\begin{aligned}
 f_{n12} &= \frac{3w_1^2 + 6.2(w_1 - w_c + 0.33)(w_1/w_d)^6}{1 + (w_1/w_d)^6} \times 10^{13} \\
 f_{n21} &= (1.5 + 1.2w_d) \times 10^{12} \\
 f_{p1} &= \frac{C_{imp} + 2.9 + 170(w_1 + w_d)(w_1/w_d)^6}{1 + (w_1/w_d)^6} \times 10^{12} \\
 f_{p2} &= 8 \times 10^{13} \sqrt{w_2} \\
 f_{w1} &= \frac{0.4 + 2.8(w_1/w_d)^8}{(w_1 + 0.2) \left[ 1 + (w_1/w_d)^8 \right]} \times 10^{12} \\
 f_{w2} &= \frac{1.2}{\sqrt{w_2}} \times 10^{12} \\
 w_{12} &= \frac{w_0 + w_c + 1.4(w_1 + w_d)(w_1/w_d)^6}{1 + (w_1/w_d)^6} \\
 C_{imp} &= 1.6 \left( \frac{N_I}{10^{19}} \right)^{0.4} \times 10^{13}
 \end{aligned}$$

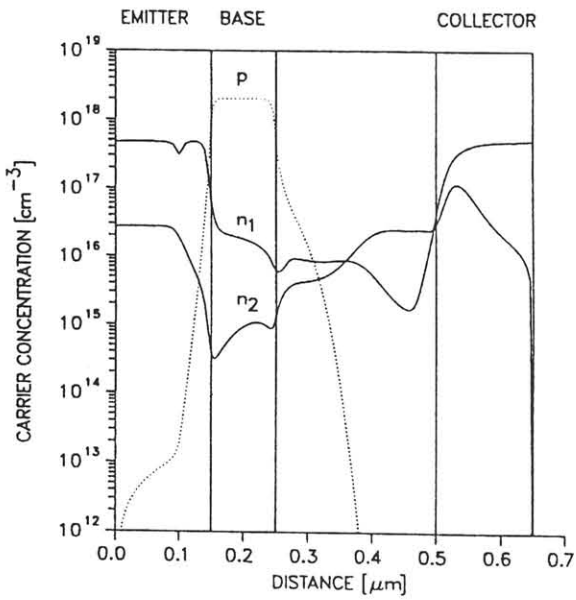
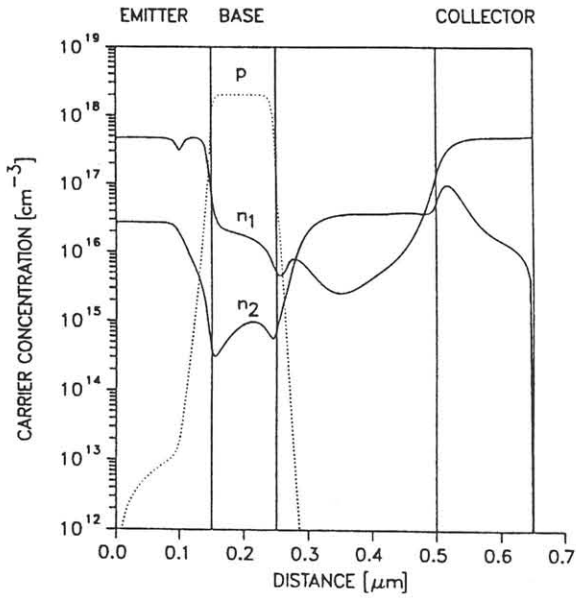
**Table.1** The interpolation formulas for various relaxation frequencies  $f$ 's and  $w_{12}$ , where  $w_c$  ( $=0.33-0.75x$ ) is the critical energy for the intervalley transfer, and  $N_I$  is the impurity concentration.

|           |   |   |
|-----------|---|---|
|           | Al <sub>0.3</sub> Ga <sub>0.7</sub> As $n=5 \times 10^{17} \text{cm}^{-3}$ 0.10 $\mu\text{m}$ |   |
| EMITTER   | x=0.3 - 0.1   | 0.05 $\mu\text{m}$  |
| BASE      | Al <sub>x</sub> Ga <sub>1-x</sub> As<br>x=0.1 - 0   | $p=2 \times 10^{18} \text{cm}^{-3}$ 0.1 $\mu\text{m}$   |
| COLLECTOR | GaAs  | $n=5 \times 10^{16} \text{cm}^{-3}$ (conv)<br>or $p=3 \times 10^{16} \text{cm}^{-3}$ (invt)<br>0.25 $\mu\text{m}$ |
|           | GaAs  | $n=5 \times 10^{17} \text{cm}^{-3}$ 0.15 $\mu\text{m}$  |

**Fig.1** AlGaAs HBT model

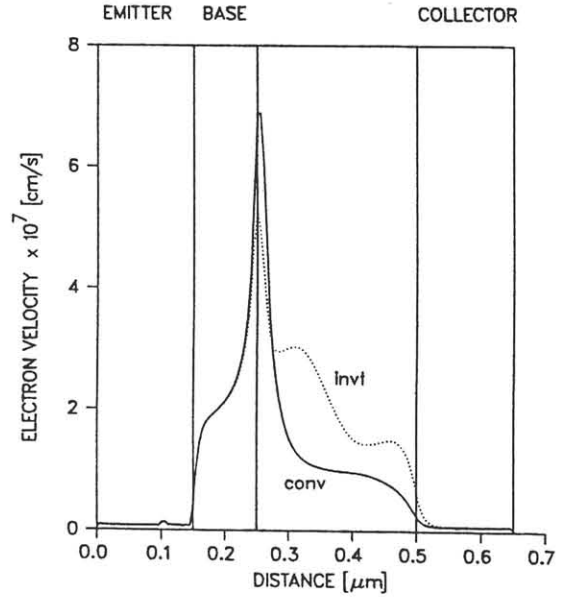
due to the inverted-field profile, where the field becomes very high closer to the  $n^+$  collector.

Fig.3 shows the corresponding profiles of the average electron velocity in the HBT<sub>conv</sub> (solid curve) and the HBT<sub>invt</sub> (dotted curve) at the bias condition. It is seen that the



**Fig.2** The carrier density profiles in HBT<sub>conv</sub> (a) and HBT<sub>invt</sub> (b). The solid curves  $n_1$  and  $n_2$  show the electron densities in the  $\Gamma$ - and L- valleys, respectively. The dotted curves show the hole density.  $V_{CE}=1.5V$  and  $V_{be}=1.37V$ .

average electron velocity  $\langle v \rangle$  increases rather steeply in the base region because electrons are accelerated by the built-in electric field.  $\langle v \rangle$  reaches a value, as high as  $2 \times 10^7$  cm/s within a short distance from the emitter-base junction. The velocity is larger by a factor of 2 than our previous results obtained by Monte Carlo HBT simulation for identical designs[2]. This difference may be caused by the fact that the pre-



**Fig.3** The profiles of the average electron velocity in the HBT<sub>conv</sub> (solid curve) and the HBT<sub>invt</sub> (dotted curve).

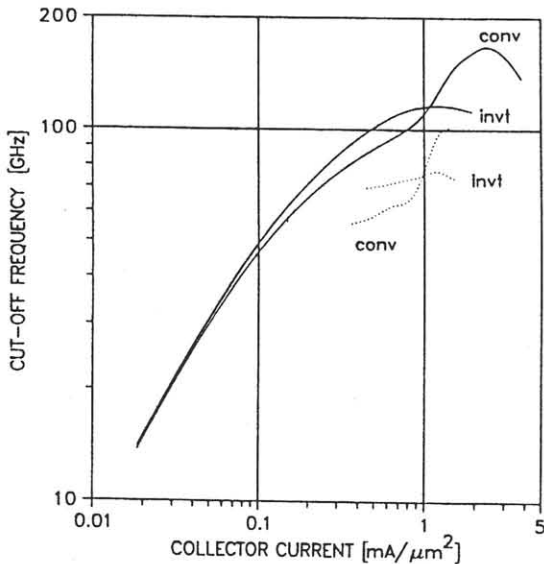
sent model does not take into account the effect of hole-plasmon scattering which was taken into account in the Monte Carlo HBT simulation.

A higher peak value of  $\langle v \rangle$  is observed in the HBT<sub>conv</sub>. This is caused by the fact that electrons injected into the SCR are accelerated more steeply by the higher electric field near the base-collector junction. However, the velocity overshoot in the SCR of the HBT<sub>conv</sub> reached only within a distance of 500Å from the base-collector junction, because intervalley transfer takes place soon after the carrier injection into the SCR. The value of  $\langle v \rangle$  is reduced afterwards to about  $1 \times 10^7$  cm/s in the remaining SCR part of the HBT<sub>conv</sub>.

The range of the velocity overshoot in case of the HBT<sub>invt</sub> is longer than for HBT<sub>conv</sub>. This is due to a gradual increase of the electric field in the SCR, which permits electrons to propagate over longer distance in the  $\Gamma$ -valley before intervalley transfer takes place.  $\langle v \rangle$  remains as high as  $3 \times 10^7$  cm/s at quite a distance from the base-collector junction. The distance and the amount

of the velocity overshoot observed in the present simulation are quite similar to those observed in the previous Monte Carlo simulation[2].

The unity-current-gain cut-off frequency  $f_T$  is calculated from the current density ( $I_C$ ) over hole charge ( $Q_h$ ) derivative. The  $f_T$  of  $HBT_{conv}$  and  $HBT_{invt}$  calculated in this way are shown by the solid curves in Fig.4. The collector bias is  $V_{CE} = 1.5V$ .  $f_T$ 's calculated by the Monte Carlo method are also shown by the dotted curves in the same figure. The Monte Carlo program used accounts for hole-plasmon scattering. The presence of this scattering mechanism results in  $f_T$  values



**Fig.4** The unity-current-gain cut-off frequency  $f_T$  for  $HBT_{conv}$  (solid curve) and for  $HBT_{invt}$  (dotted curve).  $V_{CE}=1.5V$ .

which are lower by a factor of about 0.7 than those obtained by the transport equation method. However the behavior of  $f_T$ 's as function of  $I_C$  are qualitatively same.

As shown in this section, the electron transport in HBT's and the values of  $f_T$  predicted in the presented model correlate well with those obtained by Monte Carlo simulation.

#### 4. Conclusion

The transport equations for particles, momentum and energy densities in two conduction bands are applied to a self-consistent analysis of AlGaAs/GaAs HBT's, where useful formulas for the relaxation frequencies are employed by which the variation of the conduction band energy and doping concentration in a heterostructure device are easily taken into account.

The electron transport and device performance predicted by the present approach is quite similar to the one predicted by Monte Carlo simulation, suggesting the usefulness of the present approach.

#### References

- [1] R.A.Stewart et al.; Solid-State Electronics to be published.
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